Application No. Applicant(s) KWAK ET AL. 10/601,870 Notice of Allowability Examiner **Art Unit** H.Jey Tsai 2812 -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308. 1. This communication is responsive to 2. The allowed claim(s) is/are 1-11. 3. The drawings filed on 24 June 2003 are accepted by the Examiner. 4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). b) Some* c) None of the: 1.

Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3.
☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 5. Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application) since a specific reference was included in the first sentence of the specification or in an Application Data Sheet. 37 CFR 1.78. (a) The translation of the foreign language provisional application has been received. 6. Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121 since a specific reference was included in the first sentence of the specification or in an Application Data Sheet, 37 CFR 1.78, Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 7. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient. 8. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) I including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) 🔲 hereto or 2) 🔲 to Paper No. 🔙 (b) including changes required by the proposed drawing correction filed including changes required by the Examiner. (c) 🔲 including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No. Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the margin according to 37 CFR 1.121(d). 9. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL. Attachment(s) 1⊠ Notice of References Cited (PTO-892) 5 Notice of Informal Patent Application (PTO-152) 2 Notice of Draftperson's Patent Drawing Review (PTO-948) 6 Interview Summary (PTO-413), Paper No.____ 3 Information Disclosure Statements (PTO-1449 or PTO/SB/08), 7 Examiner's Amendment/Comment Paper No. 4 Examiner's Comment Regarding Requirement for Deposit 8 Examiner's Statement of Reasons for Allowance of Biological Material 9 Other H.Jey Tsai Primary Examiner Art Unit: 2812

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Reasons For Allowance

The following is an Examiner's statement of reasons for the indication of allowable subject matter:

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The basis for the allowability is:

Claims 1-11 recites the combination of forming a trench in an isolation region of a semiconductor substrate and then forming an insulation film within the trench; forming a screen oxide film on the semiconductor then forming a triple well though an ion implantation process using a given mask; removing the screen oxide film, forming a tunnel oxide film and a first polysilicon layer and then patterning the first polysilicon to form a floating gate over the substrate in the memory cell region; forming a second polysilicon layer to form a control gate in the memory cell region; injecting an ion for controlling the threshold voltage into the exposed semiconductor substrate of the peripheral circuit region; and forming a gate oxide film and a third polysilicon layer over the semiconductor substrate of the peripheral circuit region to form a gate of transistor.

None of the art of record teaches nor suggests to combine above cited limitations in the claimed invention as a whole.

Any comments considered necessary by applicant must be submitted no later than the payment of the Issue Fee and, to avoid processing delays, should preferably **accompany** the Issue Fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Any inquiry of a general nature or clerical matters or relating to the status of this application or proceeding should be directed to the Group customer service whose telephone number is (703) 306-3329 and Fax number (703) 306-5515. Group receptionist telephone number 703-308-0956.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to H. Jey Tsai whose telephone number is (703) 308-1374. The examiner can normally be reached on from 7:00 Am to 4:00 Pm., Monday thru Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Niebling can be reached on (703) 308-3325. The fax phone number for this Group is (703) 872-9306.

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11/17/03

H. Jey Tsai

Primary Examiner
Patent Examining Group 2800